

SHEET 1 OF 2

Form PTO 1449
(Modified)U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY DOCKET NO.
217218US2PCTSERIAL NO.
10/019,278

LIST OF REFERENCES CITED BY APPLICANT

APPLICANT

Marc DELAUNAY, et al.

FILING DATE

January 2, 2002

GROUP

1762

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
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	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
					YES	NO
	AO					
	AP					
	AQ					
	AR					
	AS					
	AT					
	AU					
	AV					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

<i>W</i>	AW	A.Y. Tcherepanov et al, Flat Panel Displays Based Upon Low-Voltage Carbon Field Emitters, 7 th International Vacuum Microelectronics Conference, July 1994, vol. 50, pgs. 205-208.				
<i>W</i>	AX	D. Hong et al., Field Emission From P-Type Polycrystalline Diamond Films, 7 th International Vacuum Microelectronics Conference, Number 271, April 1994, pgs. 96-99.				
<i>W</i>	AY	M. Delaunay et al, Electron Cyclotron Resonance Plasma Ion Source for Material Depositions, Review of Scientific Instruments, vol. 69, Number 6, June 1998, pgs. 2320-2324.				
<i>W</i>	AZ	Seiichi Matsumoto, Chemical Vapour Deposition of Diamond in RF Glow Discharge, Journal of Materials Science Letters 4, 1985, pgs. 600-602.				<input checked="" type="checkbox"/> Additional References sheet(s) attached

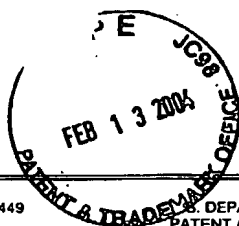
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Date Considered

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SHEET 2 OF 2

Form PTO 1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 217218US2PCT	SERIAL NO. 10/019,278
		APPLICANT Marc DELAUNAY, et al.	
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LIST OF REFERENCES CITED BY APPLICANT			
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	AAB	Sumio Iijima, Helical Microtubules of Graphitic Carbon, Letters to Nature, Vol. 354, November 7, 1991, pgs. 56-58.	
	AAC	Olivier M. Kuteel, et al., Electron Field Emission From Phase Pure Nanotube Films Grown in a Methane/Hydrogen Plasma, Applied Physics Letters, vol. 73, Number 15, October 12, 1998, pgs. 2113-2115.	
	AAD	Z.P. Huang, et al., Growth of Highly Oriented Carbon Nanotubes by Plasma-Enhanced Hot Filament Chemical Vapor Deposition, Applied Physics Letters, Vol. 73, Number 26, December 28, 1998, pgs. 3845-3847.	
	AAE	Li Yunjun et al, Field Electron Emission From Highly Graphitic Diamond Films With Ball-Like Surface Morphologies, Technical Digest of International Vacuum Microelectronics Conference, Kyomgiu, Korea August 1997, pgs. 137-140.	
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	AAG	M. Delaunay et al., Electron Cyclotron Resonance Plasma Ion Source For Material Depositions, Review of Scientific Instruments, Vol. 69, Number 6, June 1998, pgs. 2320-2324.	
	AAH	Yahachi Saito et al., High Yield of Single-Wall Carbon Nanotubes by arc Discharging Using Rh-Pt Mixed Catalysts, Chemical Physics Letters Vol. 294, September 25, 1998, pgs. 593-598.	
	AAI	S.P. Bozeman et al., Electron Field Emission From Amorphous Carbon-Cesium Alloys, J. Vac. Science Technol. A 15(3), May/June 1997, pgs. 1729-1732.	
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	AAK	Gehan A.J. Amaratunga et al., Nitrogen Containing Hydrogenated Amorphous Carbon for Thin-Film Field Emission Cathodes, Appl. Phys. Letters 68 (18), 29 April 1996, pgs. 2529-2531.	
	AAL	B.S. Satyanarayana et al., Field Emission From Tetrahedral Amorphous Carbon, Appl. Phys. Letters, 71 (10), 8 September 1997, pgs. 1430-1432.	
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	AAQ		
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